

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

icant(s) : Mark Holst et al.

Serial No. : 09/970,613

Filed : October 4, 2001

For : EFFLUENT GAS STREAM TREATMENT SYSTEM HAVING

UTILITY FOR OXIDATION TREATMENT OF

SEMICONDUCTOR MANUFACTURING EFFLUENT GASES

Group Art Unit: 1764

Customer No. : 41161

Mail Stop RCE

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Sir:

In accordance with 37 C.F.R. §§ 1.56 and 1.97, applicants wish to call the attention of the Examiner to the following references:

- U.S. Patent No. 4,296,079, Hauser
- U.S. Patent No. 4,935,212, Eberhard
- U.S. Patent No. 5,206,003, Imoto et al.
- U.S. Patent No. 5,292,704, Lester
- U.S. Patent No. 5,393,394, Ikeda et al.

U.S. Patent No. 5,877,391, Kanno et al.

Foreign Art Reference No. EP 0861683 A2 (EPO)

Foreign Art Reference No. EP 0885648 A1 (EPO)

"Catalytic Decomposition System", Hitachi America, Ltd. Semiconductor Equipment Group- SCDS Gas Abatement Systems, <http://www.hitachi.com/semiequipment/products scds.html>, pages 1-2, printed on 4/21/99.

"Kanken Techno detoxifier KT 1000 Venus", Crystec Technology Trading GmbH, >>, pages 1-4, printed on 7/27/99.

These references are also listed on the accompanying Information Disclosure Statement (Form PTO-1449).

Consideration of the foregoing in relation to this patent application is respectfully requested.

Respectfully Submitted,

Brian M. Dugan, Exq. Registration No. 41,720

Dugan & Dugan, PC

Attorneys for Applicants

(914) 332-9081

Dated:

U.S. Dep	artment c	of Commerce, Pat	III	Docket No.: 9955/D01/Y01/AGS/LP			Serial No.: 09/970,613				
LIST		EVANT ART CIT	Applicants: Mark Holst et al.								
	(Use several sheets if necessary) FEB 2.1 2006					Filing Date: October 4, 2001			Group: 1764		
U.S.	Patent D	ocuments	TOTAL T	PADEMARMS							
*Examiner Initial		Document Number	Issue Date	Nan	ne	Class		Subclass		Filing Date If Appropriate	
	US-1	4,296,079	10/20/81	Hauser							
	US-2	4,935,212	06/19/90	Eberhard							
-	US-3	5,206,003	04/27/93	Imoto et al.							
	US-4	5,292,704	03/08/94	Lester							
	US-5	5,393,394	02/28/95	Ikeda et al.							
	US-6	5,877,391	03/02/99	Kanno et al.							
	US-7										
	US-8										
	US-9			-							
	US-10										
	US-11			<u> </u>							
Fore	ign Pater	nt Documents		<u></u>				_	Tı	ranslatior	
		Document Number	Date	Coun	try	Class	Subclass		Yes	No	
	F-1	EP 0861683 A2	09/02/98	EPO	5				Х		
	F-2	EP 0885648 A1	12/23/98	EPO	5				X		
	F-3										
	F-4										
	F-5										
OTF	IER ART	(Including Auth	or, Title, Da	ate, Pertinent Page	es, Etc.)						
	OT-1	"Catalytic Decor Abatement Syste	mposition Sy ems, <a ,="" a<br="" hitachi="" href="http://v</td><td>ystem">www.hitachi.com	merica, Ltd. S /semiequipm	ent/products sed	ls.html>	, pages 1-2	SCDS Gas 2, printed or	n 4/21/99		
	OT-2	"Kanken Techno detoxifier KT 1000 Venus", Crystec Technology Trading GmbH, http://www.crystec.com/ktcvenue.htm , pages 1-4, printed on 7/27/99.									
	OT-3		Date Consid	Jana							
Examiner											
EXAMINER	र: Initial mance an	if reference considered.	idered, whet Include co	ther or not citation py of this form wi	n is in conform ith your comr	mance with MPI nunication to ap	EP 609; plicant.	Draw line	through cit	ation if	

C:\WP51\FORMS\1449.PTO 1/94
Express Mail Label No.: EV605115823US